

L Number	Hits	Search Text	DB	Time stamp
13	1		USPAT; US-PGPUB	2003/11/26 08:38
14	1		USPAT; US-PGPUB	2003/11/26 08:39
15	1		USPAT; US-PGPUB	2003/11/26 08:39
17	1		USPAT; US-PGPUB	2003/11/26 09:02
18	1		USPAT; US-PGPUB	2003/11/26 09:03
19	1		USPAT; US-PGPUB	2003/11/26 09:04
20	1		USPAT; US-PGPUB	2003/11/26 09:05
66	1	("5638211").PN.	USPAT; US-PGPUB	2003/11/26 12:29
-	86	((mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:36
-	4	((mask or photomask or reticle or PSM) same ((coherence adj factor) or coherence or "sigma")) and 430/5.ccls.) and zone adj plate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:29
-	254	((mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 or reduc\$4)) not ((mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:29
-	2611	(mask or photomask or reticle) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:30
-	3089	(mask or photomask or reticle) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or deform\$3 same (light\$3 or illuminat\$3 or radiat\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:31
-	3108	(mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:31
-	407	((mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))) and 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:31

-	258	((master or parent or original) near\$3 (mask or photomask or reticle or PSM) same ((coherenc\$3 adj factor) or coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:37
-	255	((master or parent or original) near\$2 (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:38
-	214	((master or parent or original) adj\$2 (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:39
-	7	((master or parent or original) adj (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:40
-	14	((master or parent or original or first or second) adj (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))) and 430/5.ccls. and (mask or photomask or reticle or PSM) same (enlarg\$3 and reduc\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/22 08:52
-	3129	(process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:05
-	11	((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:09
-	599	((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:06
-	179	((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:55

-	178	(((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:27
-	0	(((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((process or method or manufacture\$3 or fabricat\$4 or form\$5) same (master or parent or original or first or second or work\$3) near2 (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:21
-	3	(((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:21

-	6359	430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:53
-	2320	(430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (mask or photomask or reticle or PSM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 14:54

-	152	(430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 15:01
-	5	(430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 17:14

-	147	(430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM) not ((430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 15:02
-	1	("5861866").PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/24 16:25

<p>Search History</p> <p>C:\APPS\east\workspac</p>	<p>48</p>	<p>(430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" not ((430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or PSM)) not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) and ((mask or photomask or reticle or PSM) same (coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3)))))) and (enlarg\$5 or reduc\$3) same (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM) not ((430/5.ccls. not (((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)) same ((coherenc\$3 or "sigma" or circ\$6 adj (zon\$3 or apertur\$3) or (deform\$3 same (light\$3 or illuminat\$3 or radiat\$3 or irradiat\$3))))) not (((((process or method or manufactur\$3 or fabricat\$3 or form\$3) near2 (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle or PSM)).ti,ab.) and (enlarg\$5 or reduc\$5) same (mask or photomask or reticle or</p>	<p>USPAT; US-PGPUB; EPO; JPO; IBM_TDB</p>	<p>2003/11/26 12:29</p> <p>BEST AVAILABLE COPY</p>
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-	1	("5411823").PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 18:57
-	3	((("5031976") or ("5788229") or ("5717518")).PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:16
-	1173	430/394.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:18
-	3654	(mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:27
-	73	430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma"))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:27
-	39	(430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma")) and 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:28
-	23	((430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma"))) and 430/5.ccls.) and (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:31
-	4022	(master or parent or original or first or second or work\$3) adj (mask or photomask or reticle) same (plural or multiple or (first and second)) same (expos\$3 or radiat\$3 or irradiat\$3 or light\$3) not (((430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma"))) and 430/5.ccls.) and (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:35
-	65	((master or parent or original or first or second or work\$3) adj (mask or photomask or reticle) same (plural or multiple or (first and second)) same (expos\$3 or radiat\$3 or irradiat\$3 or light\$3) not (((430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma"))) and 430/5.ccls.) and (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle))) and (optical adj proximity adj correction or "OPC")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:36
-	43	((master or parent or original or first or second or work\$3) adj (mask or photomask or reticle) same (plural or multiple or (first and second)) same (expos\$3 or radiat\$3 or irradiat\$3 or light\$3) not (((430/394.ccls. and ((mask or photomask or reticle) same (coherent or coherenc\$4 or "sigma"))) and 430/5.ccls.) and (master or parent or original or first or second or work\$3) adj (mask or photomask or reticle))) and (optical adj proximity adj correction or "OPC")) and 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/11/25 19:36